Other Specification

Flatness

Product		Size	Surface Finish	TTV(µm)		TIR(µm)		LTV(µm)			Warp(µm)	
				Guaranteed	(Ref.) Typical	Guaranteed	(Ref.) Typical	Guaranteed	PLTV(%) Guaranteed	(Ref.) Typical	Guaranteed	(Ref.) Typical
GaAs	Semi- Insulating	6"φ	P/P	≦5	1.5	≦4	1.8	≦1.5(20mm)	≧90	0.7	≦10	3
	Laser	3"φ	P/LE	≦10	6				_		≦10	7
	Diodes	4"φ		≦10	6				_		≦10	7
InP		2"φ	P/E	≦15	10	≦12	10		_		≦15	10
			P/LE	≦6	4	≦6	4		_		≦9	5
			P/P	≦6	4	≦6	4		_		≦9	5
		3"φ	P/LE	≦8	4	≦6	5		_		≦10	7
			P/P	≦6	3	≦ 4	3		_	_	≦10	5
		4"φ	P/P	≦5	3	≦5	3	_	_		≦10	5
		6"φ	P/P	≦10	5	≦10	4	_	_		≦10	5

Definitions of Flatness

TTV	Total Thickness Variation: The difference between the highest and the lowest elevation of the top surface of a clamped wafer. The back surface referenced.	TTV
TIR	Total Indicated Reading: The difference between the highest point above and the lowest point below the front surface referenced focal plane of a clamped wafer. 3 points on the front surface generally used.	B TIR = A + B Referenced Focal Plane
LTV	Local Thickness Variation: The difference between the highest point and the lowest point within a site of the top surface of a clamped wafer. The back surface referenced.	Focal Plane Focal Plane
PLTV	Percent LTV: Percentage of sites on a wafer within the specified LTV value.	Focal Plane LTV Focal Plane
Warp	The difference between the highest point above and the lowest point below the front surface referenced focal plane of an unclamped wafer. A least square fit on the front surface generally used.	B Warp = A + B Referenced Focal Plane

Light Point Defects

Product	Size	Defect Size	Pcs./Wafer		
Product	Size	Defect Size	Guaranteed	(Ref.) Typical	
GaAs VB (Semi-Insulating)	6"φ	≧0.4µm	≦100	30	
	2"φ		≦20	7	
InP	3"φ	≧1.2µm²	≦30	10	
IIIP	4"φ		≦30	10	
	6"φ	≧0.4µm	≦100	50	